

WHAT IS CLAIMED IS:

1. An apparatus for processing a substrate, the apparatus comprising:

a housing having a process space;

a support unit configured to support the substrate in the process space;

a plasma source configured to generate plasma from a process gas; and

a baffle unit disposed over the support unit,

wherein the baffle unit includes a baffle having first holes formed therein through which the process gas and/or the plasma flows and a lower surface of the baffle is exposed to the processing space, and

wherein the baffle has second holes formed in an edge region thereof, each of which has a lengthwise direction inclined with respect to a radial direction of the baffle when viewed from above,

wherein a virtual straight line drawn from the center of the baffle along the radial direction overlaps at least one of the second holes when viewed from above,

wherein the second holes are formed in the edge region along a circumferential direction of the baffle, and wherein inclined directions of the second holes are the same.

2. The apparatus of claim 1, wherein the second holes are provided in the entire edge region of the baffle.

3. The apparatus of claim 1, wherein inclination angles formed by inclined directions of the second holes and the radial direction of the baffle are the same.

4. The apparatus of claim 1, wherein the second holes have a long narrow hole shape.

5. The apparatus of any one of claims 1, 2, 3 and 4, wherein the baffle unit further includes a cover plate disposed on the top or the bottom of the baffle, and wherein the cover plate has a shape that covers the second holes.

6. The apparatus of claim 5, wherein the cover plate has a ring shape.

7. The apparatus of claim 6, wherein the cover plate is provided to cover outer areas among inner areas and the outer areas of the second holes when viewed from above.

8. The apparatus of claim 6, wherein the cover plate is provided to cover inner areas among outer areas and the inner areas of the second holes when viewed from above.

9. The apparatus of claim 6, wherein the cover plate has one or more arc-shaped openings formed therein, and wherein the openings overlap outer areas among inner areas and the outer areas of the second holes when viewed from above.

10. The apparatus of claim 5, wherein the apparatus comprises:
a process unit including the housing and the support unit; and
a plasma generation unit including the plasma source, the plasma generation unit being configured to generate the plasma and supply the generated plasma into the process space, and wherein the plasma generation unit is disposed at the top of the process unit and further includes a plasma chamber having a plasma generation space.

11. The apparatus of claim 10, wherein the plasma generation unit further comprises a diffusion chamber disposed at the bottom of the plasma chamber and having a diffusion space, and

wherein the baffle unit is coupled to the diffusion chamber.

12. The apparatus of claim 11, wherein the baffle has a third hole formed therein into which a coupling means is inserted, and

wherein the cover plate has a coupling hole formed therein, the coupling hole being formed at a position corresponding to the third hole, wherein the coupling means is inserted into the coupling hole.

13. The apparatus of claim 12, wherein the cover plate is disposed on the bottom of the baffle.

14. A baffle unit provided in an apparatus for processing a substrate using plasma, the baffle unit comprising:

a baffle, when viewed from above, having first holes formed in a central region thereof and second holes formed in an edge region thereof, wherein the plasma flows through the first holes, and each of the second holes has a lengthwise direction inclined with respect to a radial direction of the baffle and a lower surface of the baffle is exposed to the processing space,

wherein partial areas of adjacent second holes, among the second holes, overlap each other when viewed in the radial direction of the baffle,

wherein the second holes are formed in the edge region along a circumferential direction of the baffle, and wherein inclined directions of the second holes are the same.

15. The baffle unit of claim 14, wherein the baffle unit further comprises a cover plate disposed on the top or the bottom of the baffle, and
wherein the cover plate has a ring shape to cover the second holes.

16. The baffle unit of claim 15, wherein the cover plate is provided to cover outer areas among inner areas and the outer areas of the second holes when viewed from above.

17. The baffle unit of claim 15, wherein the cover plate is provided to cover inner areas among outer areas and the inner areas of the second holes when viewed from above,
wherein the cover plate has one or more arc-shaped openings formed therein, and
wherein the openings overlap the outer areas when viewed from above.

18. The baffle unit of claim 15, wherein the baffle has a third hole formed therein into which a coupling means is inserted, and
wherein the cover plate has a coupling hole formed therein, the coupling hole being formed at a position corresponding to the third hole, wherein the coupling means is inserted into the coupling hole.